

Integrated Circuit Technology

Final Process Project

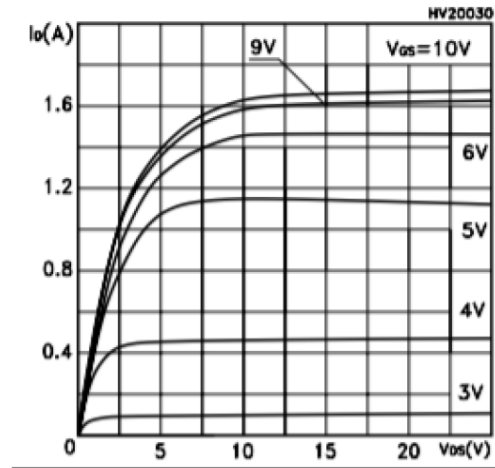
NMOS Fabrication process

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W/L calculations

- From the graph presented below the w/l has been calculated... Given $K_p = 0.08$ sec, $V_{th} = 2.1$ V
- Consider $I_d = 1.62$, $V_{gs} = 10$ V
- $W/L = 0.3244$
- Channel length is 80 μm and width is $\sim 26\mu\text{m}$

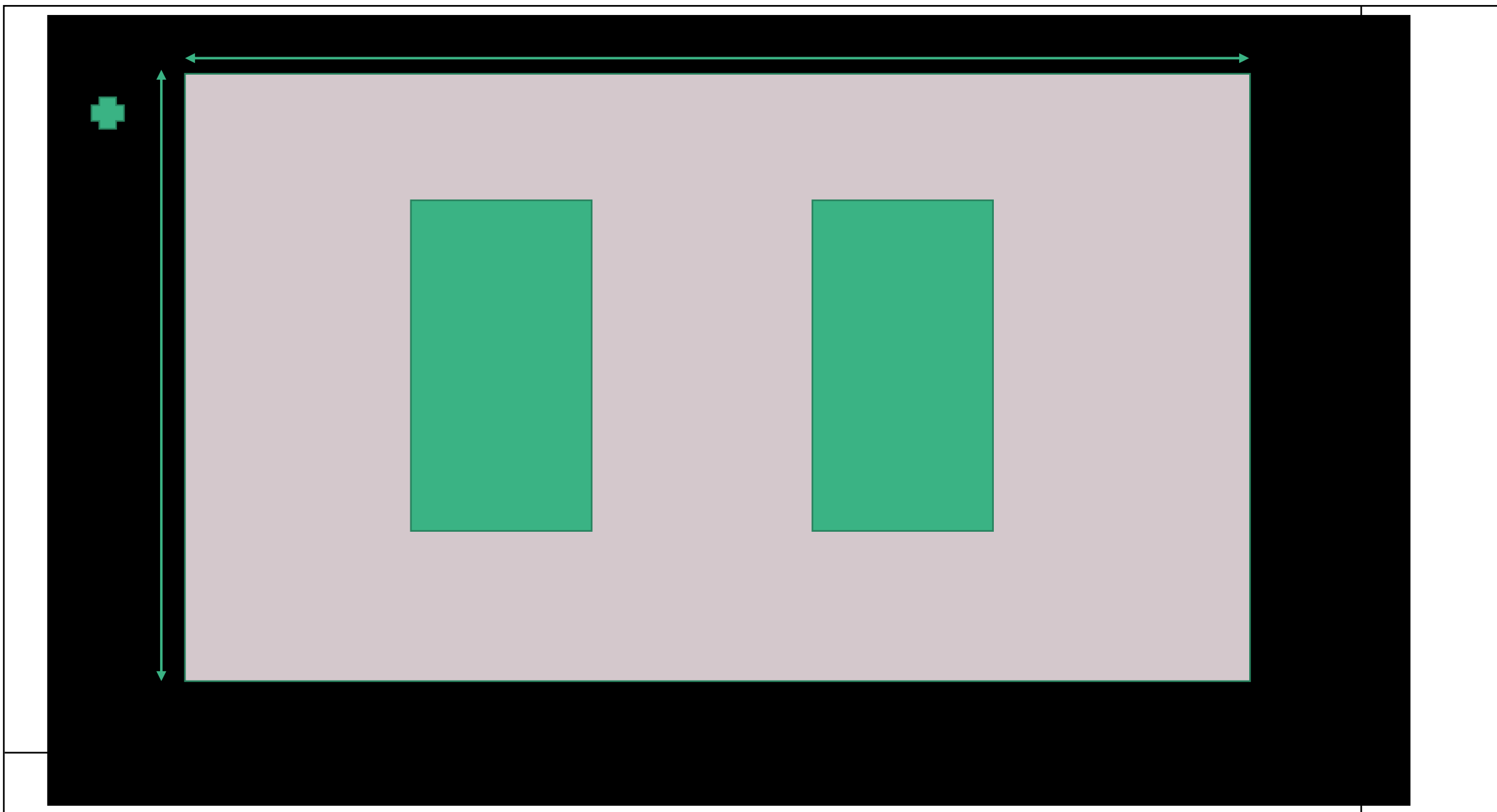


$$I_D = K_p \cdot \frac{W}{L} (V_{GS} - V_{th})^2 [A]$$

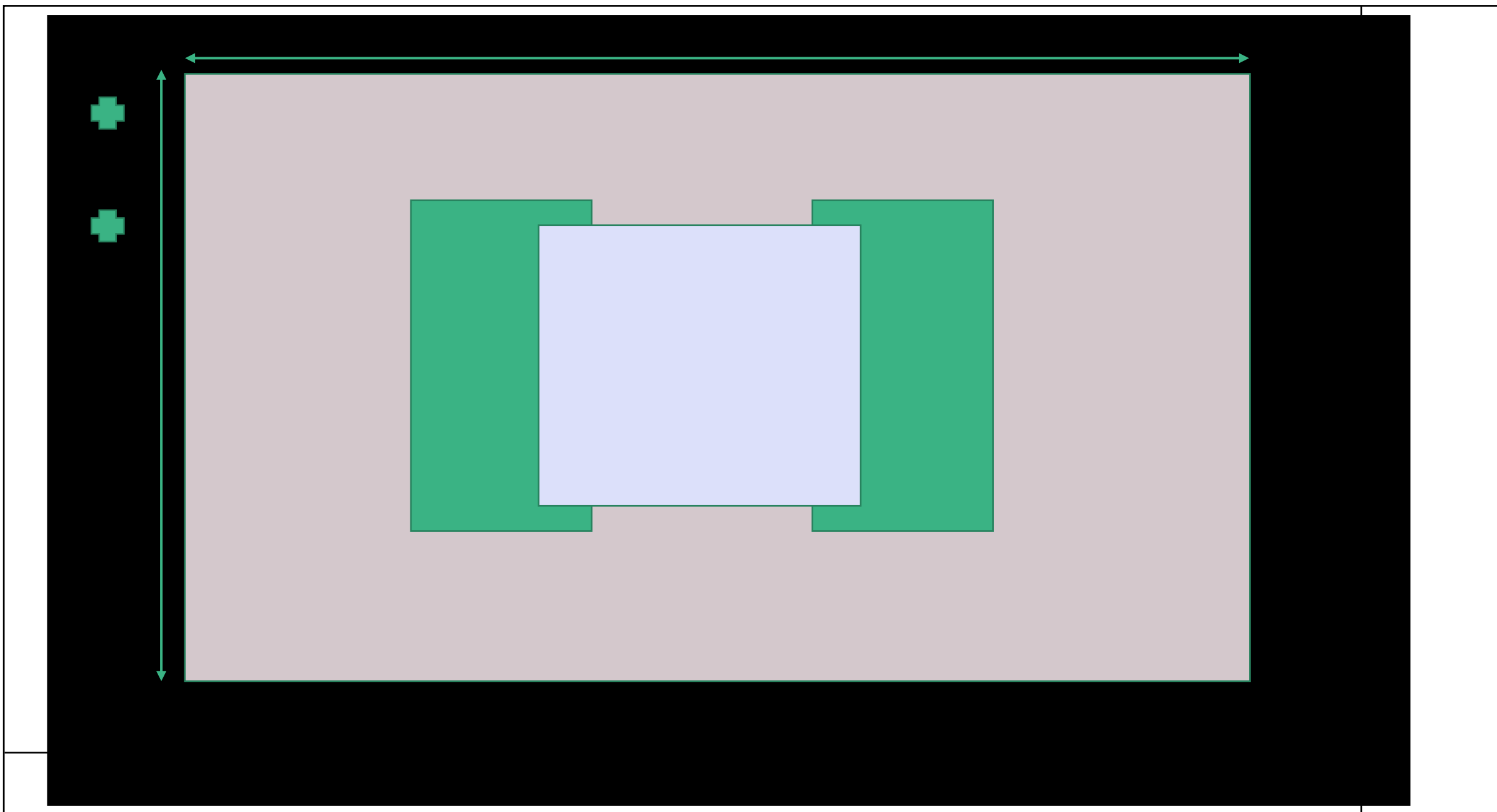
80 μm

26 μm

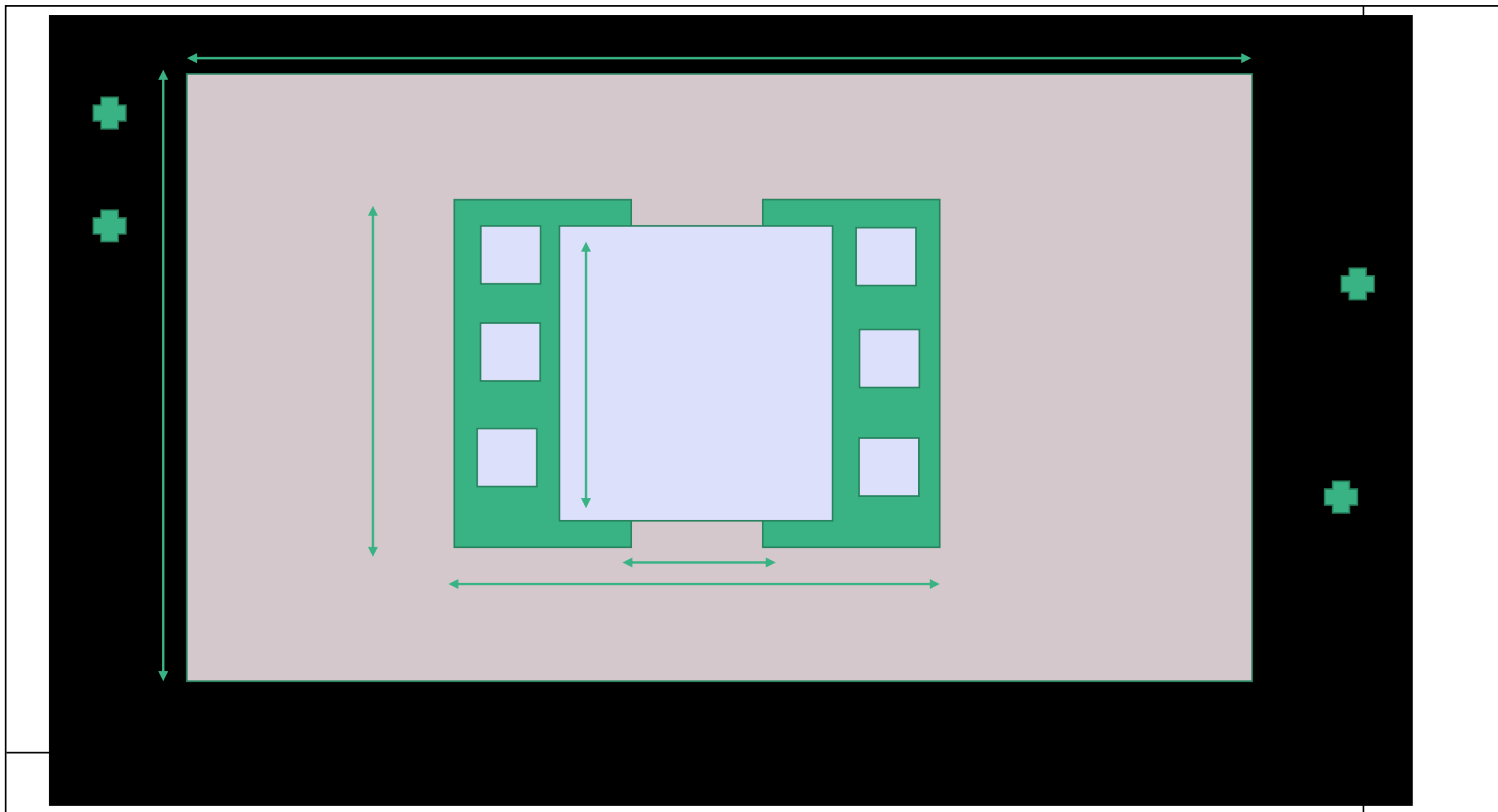
Gate measurements from the W/L calculations



Mask for Drain and Source



Gate level Mask



Metal contacts – Aluminum metal